

ABSTRACT OF THE DISCLOSURE

An alignment system for aligning a reticle having a pattern and an alignment mark with a photosensitive substrate to which the pattern of the reticle is to be transferred, is disclosed. The alignment system includes a movable substrate stage for holding the substrate, and a light-transparent plate having a mark for relative positioning with respect to at least one of the reticle and the substrate stage, wherein positioning of at least one of the reticle and the substrate stage is performed on the basis of the mark provided on the light-transparent plate.

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